### Simulation of SRAM SEU Sensitivity at Reduced Operating Temperatures

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Findings

**Abstract:** A new NanoTCAD-to-Spectre interface is applied to perform mixed-mode SEU simulations of an SRAM cell. Results using newly calibrated TCAD cold temperature substrate mobility models, and BSIM3 compact models extracted explicitly for the cold temperature designs, indicate a 33% reduction in SEU threshold for the range of temperatures simulated.



Measured Low

PMOS - Oxygen PMOS - Carbon

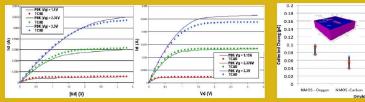
#### **Motivation**

- Limited available analyses indicate that single event response may be exacerbated by cold temperature<sup>1-3</sup>
- Desire to understand worst case SEU threshold of CMOS SRAM in mixed signal system designed using IBM 5AM SiGe BiCMOS<sup>4</sup> to know if higher level mitigation is sufficient approach

### **Methodology**

Calibrate 3D NanoTCAD model vs: PDK/Spectre-generated IV curves

# Charge collection measured on transistors<sup>5</sup>



- Simulate the temperature dependence of SEU thresholds of SRAM cell using mixed-mode using:
- A new NanoTCAD-to-Spectre interface
- BSIM3 models extracted explicitly for the cold temp design
- Newly calibrated TCAD cold temp substrate mobility models
- Lombardi model<sup>7</sup> for MOSFETs with modifications to how internal values are calculated at low temperatures, based on the models in Selberherr<sup>8</sup>.
- Altermatt model<sup>9,10</sup> for incomplete ionization, that internally calls newer effective mass and bandgap model<sup>11</sup>.



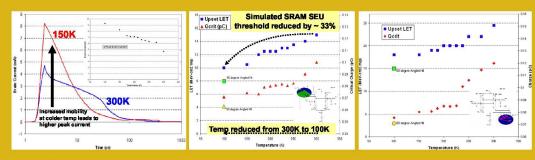
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## Peak SE-induced current increases with decreasing temperature Simulations indicate ~ 33% reduction in upset threshold for the upset increases with decreasing temperature

► Simulations indicate ~ 33% reduction in upset threshold for the range of temperatures simulated.

► The simulated minimum threshold, even for an angled (60°) strike, is well above the threshold for direct ionization by protons (equivalent to LET ~ 0.5 MeV-cm<sup>2</sup>/mg).



### **Conclusions**

► Use of common higher-level mitigation techniques for SEU is sufficient in this technology and design; no cell level hardening required

► Temperature should be considered when possible and appropriate in testing and analyses of single event effects<sup>6</sup>

Capability to couple TCAD to Spectre allows mixed mode simulations using vendor supplied PDK compact models directly

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